

Maskless Lithography Workshop

September 3rd, 2025

Sendai, Japan

Place	Tohoku University, Micro System Integration Center (μSIC) 519-1176, Aramaki Aza Aoba, Aoba-ku, Sendai-City, Miyagi, JAPAN
Organizer	Tohoku University Heidelberg Instruments KK (Co-organizer)

Agenda | Seminar |

Time	Topic
13:30 h	Registration
13:45 h	Welcome and introduction to Tohoku University <i>Kentaro Totsu, μSIC, Tohoku University</i>
14:00 h	Latest upgrades of the MLA 150 and DWL 66⁺ Laser Lithography Systems <i>Sven Preuss, Product Manager DWL-Series</i> <i>Heidelberg Instruments Mikrotechnik</i>
14:40 h	Overview of MLA 150 utilization at Tohoku University and evaluation of photoresist: a case study on SU-8 3005 <i>Yoko Furubayashi, μSIC, Tohoku University</i>
15:00 h	GenISys BEAMER application for laser direct writing <i>Satoshi Shimizu, GenISys K.K.</i>
15:30 h	Coffee break
15:50 h	Reticle fabrication on DWL 2000 with BEAMER correction <i>Masaaki Moriyama, μSIC, Tohoku University</i>
16:20 h	NanoFrazor, modular nanolithography system <i>Simon Bonanni, Exploring nanofabrication with the NanoFrazor</i> <i>Heidelberg Instruments Nano</i>
16:40 h	Introduction of Hands-on-access Fab, μSIC <i>Kentaro Totsu, μSIC, Tohoku University</i>
17:00 h	Wrap up
17:10 h	End

All sessions include a Q&A session.